



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Group Art Unit: 1732

**Brian W. Baird, Michael J. Wolfe,
Richard S. Harris, Kevin P. Fahey,
Lian-Cheng Zou, and Thomas R. McNeil**

Application No. 10/017,497

Filed: December 14, 2001

For: **ULTRAVIOLET LASER ABLATIVE PATTERNING
OF MICROSTRUCTURES IN SEMICONDUCTORS**

Examiner:

Date: December 6, 2002

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INFORMATION DISCLOSURE STATEMENT

TO THE COMMISSIONER FOR PATENTS:

Pursuant to their duty of disclosure, applicants enclose copies of the documents listed on the accompanying Form PTO-1449.

1. This information disclosure statement is being submitted:

- a. ☒ Within three months of the filing date of the above-identified application or within three months of the date of entry of the national stage, or before the mailing date of the first Office action on the merits, whichever event occurs last. (No statement under 37 CFR 1.97(e) is required.)
- b. ☐ After the period set forth in paragraph 1a, but before the mailing date of either a final action or a notice of allowance. (Check box i. or ii.)
 - i. A \$240.00 information disclosure statement submission fee set forth in 37 CFR 1.17(p) is enclosed.
 - ii. ☐ A statement specified by 37 CFR 1.97(e) is set forth below.
- c. ☐ After the mailing date of a final action or notice of allowance and on or before payment of an issue fee. A statement specified by 37 CFR 1.97(e) is set forth below. A petition requesting consideration of the information

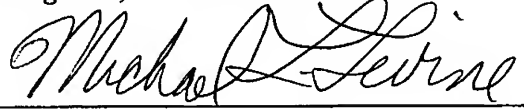
disclosure statement and the \$130.00 petition fee set forth in 37 CFR 1.17(i) are enclosed.

2. ☐ The attorney or agent signing below hereby states that:
- ☐ each item of information contained in the information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of the information disclosure statement.
- ☐ no item of information contained in the information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application, and, to the knowledge of the person signing the statement after making reasonable inquiry, no item of information contained in the information disclosure statement was known to any individual designated in 37 CFR 1.56(c) more than three months prior to the filing of the information disclosure statement.
3. ☐ Applicant(s) set forth below concise explanations of the relevance of each document not in the English language and/or selected document(s) in the English language.

Respectfully submitted,

**Brian W. Baird, Michael J. Wolfe,
Richard S. Harris, Kevin P. Fahey,
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By:



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FORM PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.
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INFORMATION DISCLOSURE CITATION
(Uses several sheets if necessary)APPLICANTS
Baird et al.FILING DATE
December 14, 2001GROUP
1732

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	DA	6,130,009	10/10/2000	Smith et al.	430	1	
	DB	5,843,363	12/01/1998	Mitwalsky et al.	264	400	
	DC						
	DD						
	DE						
	DF						
	DG						
	DH						
	DI						
	DJ						
	DK						

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FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	DL							
	DM							

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

	DN	Written Opinion concerning corresponding International Application No. PCT/US02/00867.
	DO	
	DP	

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.